## Reductive and Non-reductive Insertions of Silicon Atoms into Carbaborane Cages: Synthesis and Structure of a Carbaborane Analogue of Bis(cyclopentadienyl)silicon

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The silacarbaboranes  $[(Me_3Si)_2C_2B_4H_4]Si^{\mu}(1)$  and  $[(Me_3Si)_2C_2B_4H_4]_2Si^{\nu}(2)$  have been prepared and the structure of (2) has been determined by X-ray crystallography.

The group 4 atoms (Ge, Sn, and Pb) in their +2 oxidation states have been inserted into carbaborane cages.1 The reactions involving these atoms in their +4 oxidation states generated bridge-substituted complexes in which the heteroatom was n<sup>2</sup> linked to the carbaborane cages by a three-centre B-M-B bond.<sup>2</sup> The only reported example in which a group 4 atom is in a doubly bridged position is  $\mu, \mu'$ -SiH<sub>2</sub>(C<sub>2</sub>B<sub>4</sub>H<sub>7</sub>)<sub>2</sub>.<sup>3</sup> Recently, preliminary results on the syntheses and structures of carbaborane analogues of bis(cyclopentadienyl)germanium,  $[(Me_3Si)_2C_2B_4H_4]_2Ge$ , and bis(cyclopentadienyl)silicon, [C<sub>2</sub>B<sub>9</sub>H<sub>11</sub>]<sub>2</sub>Si, have been reported by Hosmane et al.<sup>4</sup> and Hawthorne et al.<sup>5</sup> In both compounds, the group 4 atom is in its +4 oxidation state and ten-co-ordinated. We report (i) the first reductive insertion of Si into the carbaborane cage to prepare [(Me<sub>3</sub>Si)<sub>2</sub>C<sub>2</sub>B<sub>4</sub>H<sub>4</sub>]Si<sup>II</sup> (1), (ii) a synthesis of [(Me<sub>3</sub>- $S_i$ <sub>2</sub> $C_2B_4H_4$ <sub>2</sub> $Si^{IV}$ (2) via a non-reductive insertion of Si, and (iii) the crystal structure of (2).

Both (1) and (2) were isolated in 1.0 and 18% yields, respectively from a reaction involving SiCl<sub>4</sub> and Na+Li+[(Me<sub>3</sub>Si)<sub>2</sub>C<sub>2</sub>B<sub>4</sub>H<sub>4</sub>]<sup>2-</sup> in tetrahydrofuran (THF).† The proposed structure of (1) (Figure 1) is consistent with its spectroscopic data‡ which are quite similar to those of stannacarbaboranes<sup>1f</sup> and germacarbaboranes.<sup>4</sup> The reductive insertion of Si into a carbaborane cage in the synthesis of

(1) would be expected, since tin and germanium atoms, in the same series, undergo reduction from +4 to +2 oxidation states during the syntheses of stannacarbaboranes<sup>6</sup> and germacarbaboranes,<sup>4</sup> respectively. Furthermore, the structure of bis-(pentamethylcyclopentadienyl)silicon, the first  $\pi$ -complex with Si<sup>II</sup> as the central atom, is now well documented by X-ray crystallography.<sup>7</sup>

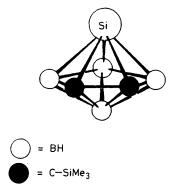
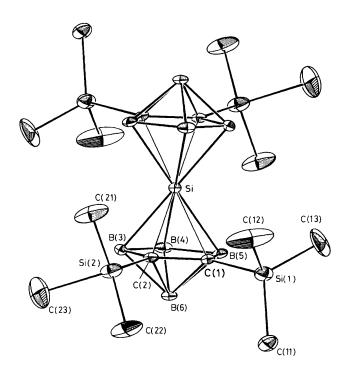


Figure 1. Proposed structure of (1).

 $\dagger$  A THF solution of Na<sup>+</sup>[(Me<sub>3</sub>Si)<sub>2</sub>C<sub>2</sub>B<sub>4</sub>H<sub>5</sub>]<sup>-</sup> (5.92 mmol) was added to a THF solution of BuLi (6.0 mmol) in vacuo and the resulting mixture was allowed to react with SiCl<sub>4</sub> (2.96 mmol) with constant stirring at 0 °C for 6 h. After removal of THF at 0 °C via vacuum distillation for 4 h, the reaction flask was attached to a high-vacuum U-trap sublimator. With identical sublimation procedures and times as described for stannacarbaboranes¹f compound (1) (0.061 mmol), as an air-sensitive colourless liquid, compound (2) (0.52 mmol), as moderately air-stable transparent crystals, and nido-[(Me<sub>3</sub>Si)<sub>2</sub>-C<sub>2</sub>B<sub>4</sub>H<sub>6</sub>] (2.48 mmol) were obtained in traps held at 0, 25, and -23 °C, respectively. Compounds (1) and (2) (m.p. 118 °C) are highly soluble in both polar and non-polar organic solvents.

‡ The mass spectra of both (1) and (2) exhibit characteristic groupings corresponding to their molecular ions, and the i.r. spectra are identical to those of corresponding germanium analogues. Fourier transform n.m.r.: (1), <sup>1</sup>H (CDCl<sub>3</sub>, relative to external Me<sub>4</sub>Si)  $\delta$  3.8 [q (br. overlapping), 3H, basal H<sub>t</sub>, <sup>1</sup>J(<sup>1</sup>H-<sup>11</sup>B) 110 Hz], 0.73 [q (br.), 1H, apical  $H_t$ ,  ${}^{1}J({}^{1}H-{}^{11}B)$  170 Hz], and 0.43 [s(br.), 18H, Me<sub>3</sub>Si];  ${}^{11}B$ (CDCl<sub>3</sub>, p.p.m. relative to external BF<sub>3</sub>·OEt<sub>2</sub>) δ 15.56 [d, 2B, basal BH,  ${}^{1}J({}^{11}B-{}^{1}H)$  160 Hz], 6.82 [d, 1B, basal BH,  ${}^{1}J({}^{11}B-{}^{1}H)$  150 Hz], and -16.79 [d, 1B, apical BH, 1J(11B-1H) 175 Hz]; 13C (CDCl<sub>3</sub>, relative to external Me<sub>4</sub>Si) δ 110.43 [s(br.), cage C] and 2.41 [q, Me<sub>3</sub>Si,  ${}^{1}J({}^{13}C^{-1}H)$  120 Hz]; (2),  ${}^{1}H$  (CDCl<sub>3</sub>, relative to Me<sub>4</sub>Si)  $\delta$  3.86 [q (br. overlapping), 6H, basal H<sub>t</sub>,  ${}^{1}J({}^{1}H^{-1}B)$  110 Hz], 0.91 [q(br.), 2H, apical  $H_1$ ,  ${}^1J({}^1H-{}^{11}B)$  170 Hz], and 0.41 [s(br.), 36H, Me<sub>3</sub>Si];  ${}^{11}B$ (CDCl<sub>3</sub>, p.p.m. relative to external BF<sub>3</sub>·OEt<sub>2</sub>)  $\delta$  20.39 [d, 4B, basal BH, <sup>1</sup>J(<sup>11</sup>B–<sup>1</sup>H) 110 Hz], 4.16 [d, 2B, basal BH, <sup>1</sup>J(<sup>11</sup>B–<sup>1</sup>H) 112 Hz], and -43.35 [d, 2B, apical BH, <sup>1</sup>J(<sup>11</sup>B-<sup>1</sup>H) 156 Hz]; <sup>13</sup>C (CDCl<sub>3</sub>, relative to external Me<sub>4</sub>Si)  $\delta$  123.85 [s(br.), cage C] and 1.36 [q,  $Me_3Si$ ,  ${}^1J({}^{13}C{}^{-1}H)$  120 Hz];  ${}^{29}Si$  (CDCl<sub>3</sub>, p.p.m. relative to external  $Me_4Si$ )  $\delta -1.25$  [m,  $Me_3Si$ ,  ${}^2J({}^{29}Si-{}^{1}H)$  6.1 Hz], -137.92 [s(br.), cage



**Figure 2.** ORTEP view of (2) showing the atomic numbering scheme. Bond distances involving the central Si atom are: Si-C(1) 2.23(1), Si-C(2) 2.25(1), Si-B(3) 2.10(1), Si-B(4) 2.03(1), and Si-B(5) 2.10(1) Å.

The X-ray crystal structure of (2),§ shown in Figure 2, reveals that the silicon atom adopts an essentially  $\eta^5$ -bonding posture with respect to each of the  $C_2B_3$  faces. However, the Si–C distances of 2.23(1) and 2.25(1) Å are substantially longer than the Si–B distances [2.10(1), 2.03(1), and 2.10(1) Å]. This type of slippage from  $\eta^{10}$  to  $\eta^6$  has been observed in the structures of  $[(Me_3Si)_2C_2B_4H_4]_2Ge^{IV}$ ,  $\{[C_2B_9H_{11}]_2Si^{IV}$ , and  $(Me_5C_5)_2Si^{II}$ . The  $[C_2B_4H_4]^2$ —moiety is isoelectronic with  $[C_5H_5]$ —by contributing 16 valence electrons [3 and 2 electrons from each of the C(R) and BH groups, respectively] to the cage or ring. Consequently, (2) can be regarded as an analogue of  $(Me_5C_5)_2Si^{II}$  which also features an  $\eta^{10}$ -bonded Si atom and possesses 32 valence electrons.

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 $c = 13.486(2) \text{ Å}, \beta = 90.72(2)^{\circ}, U = 1560.9(6) \text{ Å}^{3}, \text{ monoclinic, space}$ group  $P2_1/n$ , Z = 2,  $D_c = 0.986$  g cm<sup>-3</sup>,  $\mu(\text{Mo-}K_{\alpha}) = 2.27$  cm<sup>-1</sup>. Data were collected on a Syntex P2<sub>1</sub> diffractometer to  $2\theta = 43^{\circ}$ . No decay was observed. The data were corrected for Lorentz-polarisation, but not for absorption. 1804 unique reflections were measured of which 1021 were considered as observed  $[I > 3\sigma(I)]$  and only these were used subsequently. Refinement started with the co-ordinates of the non-H atoms of its Ge analogue, these two compounds being isostructural. All non-H atoms were refined anisotropically. None of the methyl H atoms could be located but the four cage H atoms were located and refined isotropically. Final full-matrix least-squares refinement converged to R = 0.088 and  $R_w = 0.095$ . Atomic co-ordinates, bond lengths and angles, and thermal parameters have been deposited at the Cambridge Crystallographic Data Centre. See Notice to Authors, Issue No. 1, 1986.

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